

GAS FEEDING DEVICE AND DEPOSITION FILM FORMING
APPARATUS EMPLOYING THE SAME

ABSTRACT OF THE DISCLOSURE

Provided is a gas-feeding device for feeding a starting gas for deposition-film-formation by the chemical vapor deposition method, comprising a container having a space for discharging the starting gas containing an organometallic compound by introduction of a carrier gas; a gas-introducing means connected to the container and having a plurality of gas-introducing openings for introducing the the carrier gas or the starting gas into the container to generate the starting gas; and a gas generation-accelerating means for accelerating the generation of the starting gas.

FIGURE 1